

"Rules" of low noise amplifier systems

- Combine uncorrelated noise sources in quadrature

$$e_{\text{tot}}^2 = e_1^2 + e_2^2 + e_3^2 + \dots + i_n^2 R^2 + \dots$$

follows from Campbell's theorem

consider as combinations of gaussian distributions

- First stage of amplifier dominates

noise originates at input

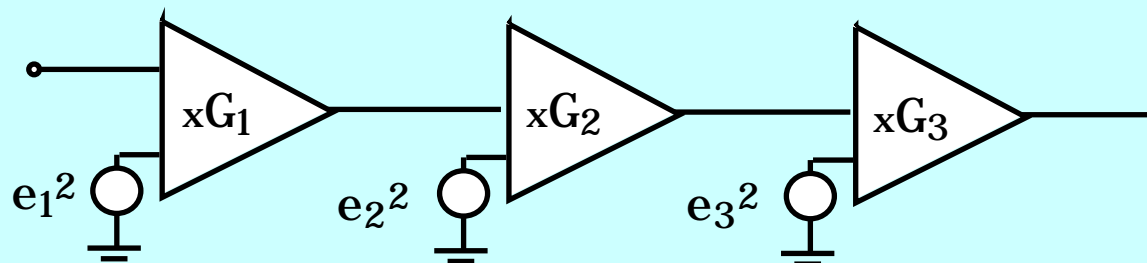
- Noise is independent of amplifier gain or input impedance

so noise can be referred to input

- In real systems both are approximations - but normally good ones

so often sufficient to focus on input device

Amplifiers - dominance of input stage



- Amplifier systems (and amplifiers!) usually consist of several stages

impractical to put all gain at one location - power, heating, material, size,...

- Calculate signal and noise at output

$$S_{\text{out}} = G_1 \cdot G_2 \cdot G_3 S_{\text{in}} \quad \text{for 3 stage system, but can easily extend to } N$$

$$(e_{\text{out}})^2 = G_1^2 \cdot G_2^2 \cdot G_3^2 e_1^2 + G_2^2 \cdot G_3^2 e_2^2 + G_3^2 e_3^2$$

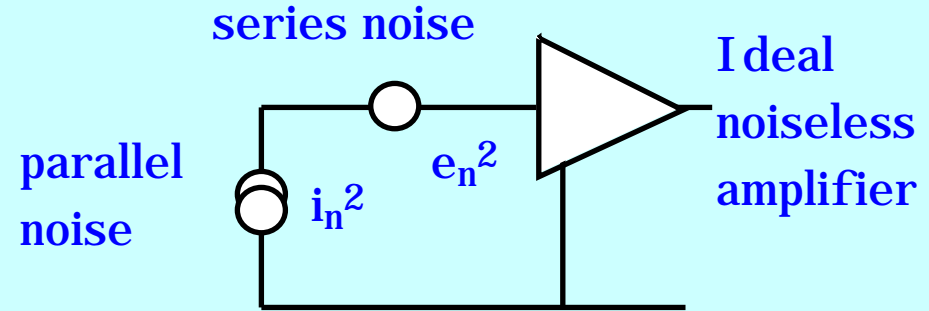
$$(e_{\text{out}} / S_{\text{out}})^2 = (e_1^2 + e_2^2 / G_1^2 + e_3^2 / G_1^2 \cdot G_2^2) / S_{\text{in}}^2$$

- Desirable to maximise gain at input stage

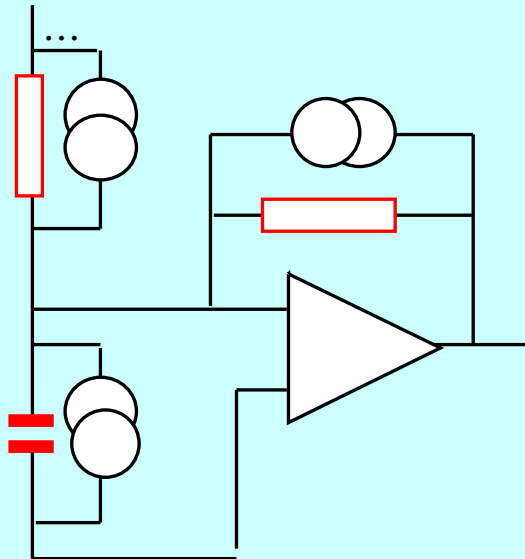
eg stage 1 boosts signal enough for transmission down cable and should be large enough that environmental noise is not significant

Amplifiers - location of noise sources

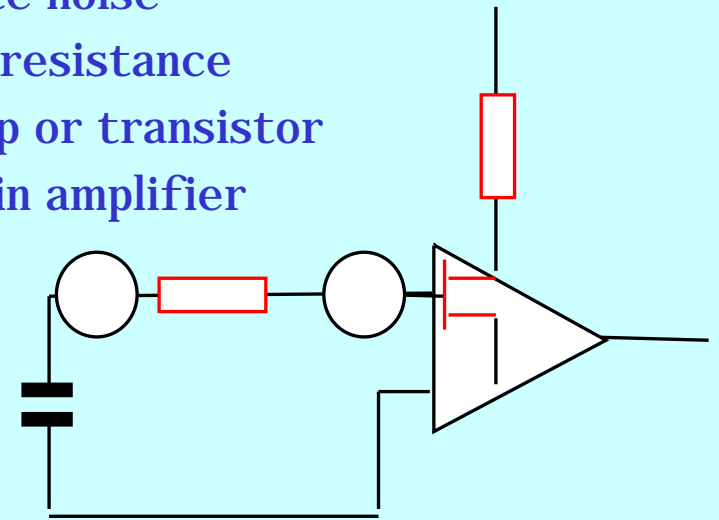
- **Normal to partition noise sources**
not fundamental to calculations
but can simplify!



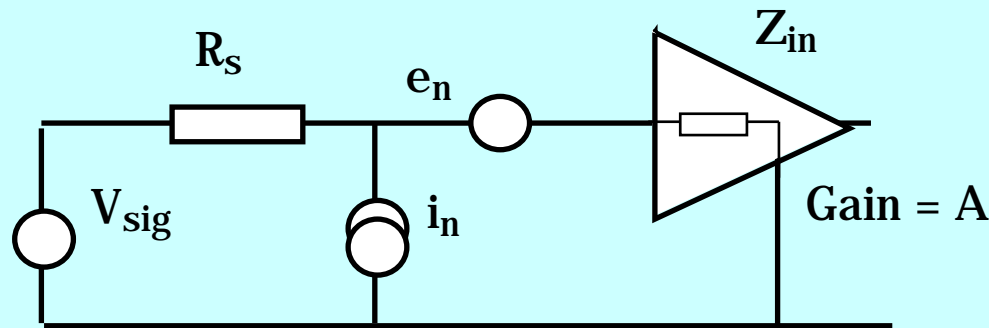
- **Parallel noise sources** appear as currents at input
detector leakage current
bias resistors
feedback resistor



- **Series noise sources** appear as voltage at input
transistor gate noise
device series resistance
microstrip or transistor
load resistor in amplifier
...



Amplifiers - reference to input



assume:
 signal source and associated impedance
 noise sources
 amplifier with gain & input impedance

• noise at output

$$E_{no}^2 = A^2 \left\{ e_n^2 Z_{in}^2 / (Z_{in} + R_s)^2 + i_n^2 R_s^2 Z_{in}^2 / (Z_{in} + R_s)^2 \right\}$$

• transfer function

$$K = V_{out} / V_{in} = A \cdot V_{sig} \cdot Z_{in} / (Z_{in} + R_s) V_{sig} = A Z_{in} / (Z_{in} + R_s)$$

• noise at input

$$E_{ni}^2 = E_{no}^2 / K^2 \Rightarrow E_{ni}^2 = e_n^2 + i_n^2 R_s^2 \quad \underline{\text{no } Z_{in} \text{ or } A \text{ dependence}}$$

easy to show analogous result $I_{ni}^2 = i_n^2 + e_n^2 / R_s^2$ choice is for convenience

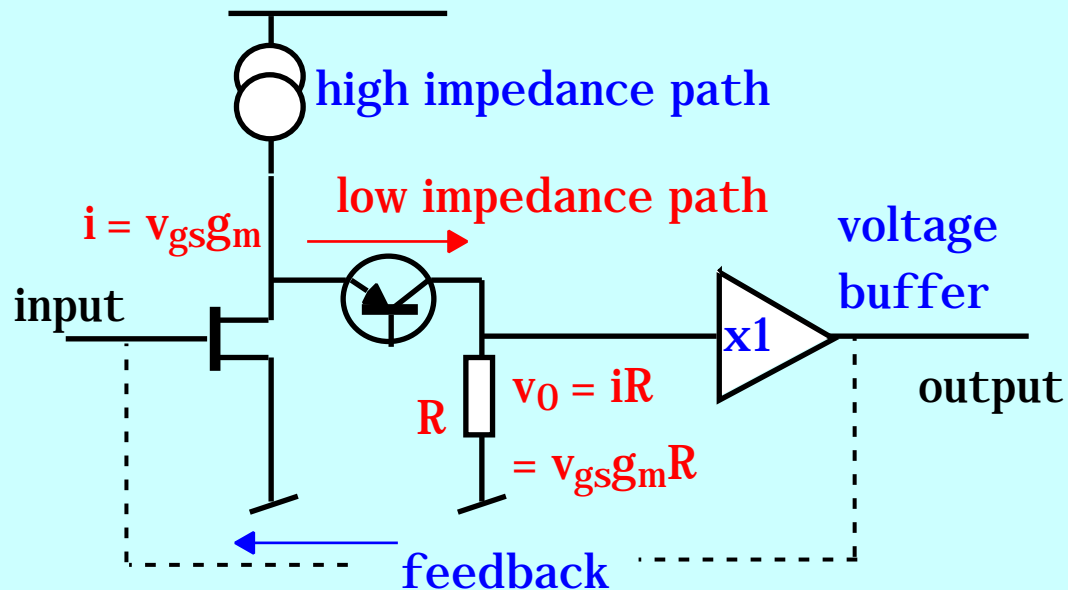
in most detector systems, there is a current signal source and a parallel capacitance

• then the spectral distribution of noise at the input is affected

$$I_{ni}^2 = i_n^2 + e_n^2 \omega^2 C^2 \quad \underline{\text{no longer white}}$$

Real amplifiers

- The first amplifier stage dominates - reason for distinction of pre-amplifier
most low-noise amplifiers are based on very simple concepts



voltage amplifier
 $G = g_m R$

add feedback to define type
eg. charge or current sensitive

within the preamplifier we expect the input device to be the most important

- To understand noise performance we need to study input device
bipolar or FET

Bipolar transistor noise

- **Two shot noise sources**

Fluctuations in I_C $i_c^2 = 2eI_C f$

Fluctuations in I_B $i_b^2 = 2eI_B f$

but these are correlated since $I_B = I_C/\beta$

- **Thermal noise in base & contacts** $e_b^2 = 4kTr_b f$

r_b = base spreading resistance

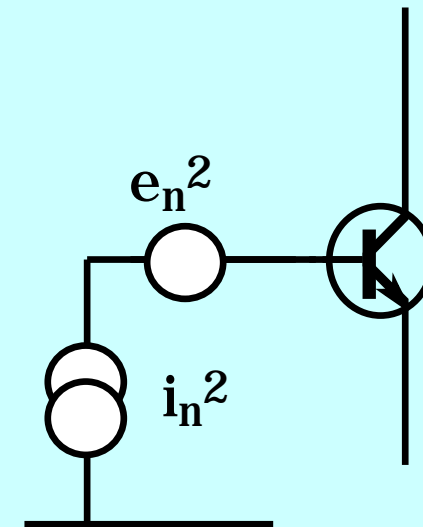
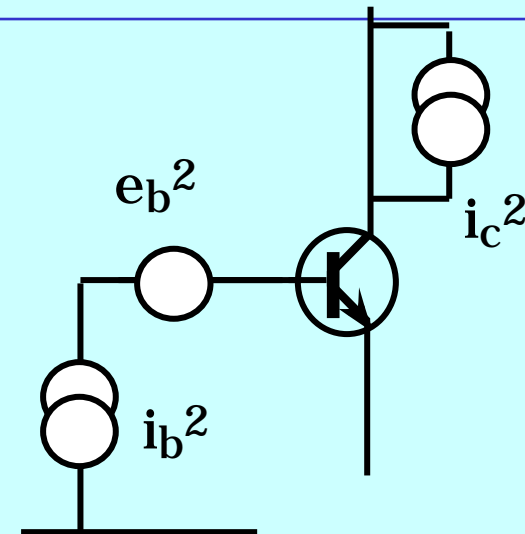
- **Transfer noise sources to input**

use $v_{be} = i_c r_e = (kT/qI_c)i_c$

$e_n^2 = (4kTr_b + 2qI_c r_e^2) f = [4kTr_b + 2(kT)^2/qI_c] f$

$i_n^2 = 2eI_B f$

- **The constraint that i_n^2, e_n^2 are correlated gives a limited range of noise with best performance for high speed applications**



Some useful numerical values

$$kT/e \quad 0.025 \text{ V} = 25\text{mV} \quad \text{at } 293\text{K} \quad (\text{Room temperature})$$

$$e = 1.6 \cdot 10^{-19} \text{ coulomb}$$

- Parallel noise - what resistor is equivalent to given current?

$$4kT/R_p = 2eI$$

$$I = 2(kT/e)(1/R_p) = 50\text{mV}/R$$

$$\text{eg, } 1\text{M} \quad 50\text{nA}$$

- Parallel noise spectral density - units and magnitudes

$$i_n = [2eI_B]^{1/2} = [32e^{-18}I_B]^{1/2} = 0.6I_B^{1/2} \text{ nA}/\sqrt{\text{Hz}}$$

$$\text{eg, } 3\text{A} \quad 1\text{nA}/\text{Hz} \quad 3\mu\text{A} \quad 1\text{pA}/\text{Hz}$$

- Series noise spectral density - units and magnitudes

$$e_n = [4kTR_s]^{1/2} = [4(kT/e)eR]^{1/2} = [1.6 \cdot 10^{-20}R]^{1/2} = 0.13R^{1/2} \text{ nV}/\sqrt{\text{Hz}}$$

$$\text{eg, } 60 \quad 1\text{nV}/\text{Hz}$$

Bipolar noise example

• r_b is often small so neglect

	$I_C = 1\text{mA}$ $I_B = 10\mu\text{A}$	$I_C = 100\mu\text{A}$ $I_B = 1\mu\text{A}$
$\beta = 100$		
$e_n = [2(kT)^2/qI_C]^{1/2}$ $= [2(kT/q)^2(q/I_C)]^{1/2}$	0.45 nV/ Hz	1.4 nV/ Hz
$i_n = [2qI_B]^{1/2}$	1.8 pA/ Hz	0.6 pA/Hz
$i_n R_S$ for $R_S = 1\text{k}$	1.8 nV/ Hz	0.6 nV/Hz
$[4kTR_S]^{1/2}$ for $R_S = 1\text{k}$	4.0 nV/ Hz	4.0 nV/ Hz
NF for $R_S = 1\text{k}$	0.84 dB	0.59 dB

• Noise figure - often used to characterise voltage amplifier performance

$$\text{NF [dB]} = 10\log_{10}(\text{Total noise power at input}/\text{Source noise power})$$

$$= 10\log_{10}\left(\frac{e_n^2 + i_n^2 R_s^2 + 4kTR_s}{4kTR_s}\right) = 10\log_{10}\left(1 + \frac{e_n^2 + i_n^2 R_s^2}{4kTR_s}\right)$$

MOSFET Noise

- Gate current shot noise

$$i_g^2 = 2eI_G f \quad \text{negligibly small for most applications}$$

high impedance of gate oxide (insulator) to substrate

- Thermal noise inside the transistor

thermal current fluctuations in channel (- but **not** shot)

$$i_d^2 = (4kT/R_n) f = 4kT(2/3)g_m f$$

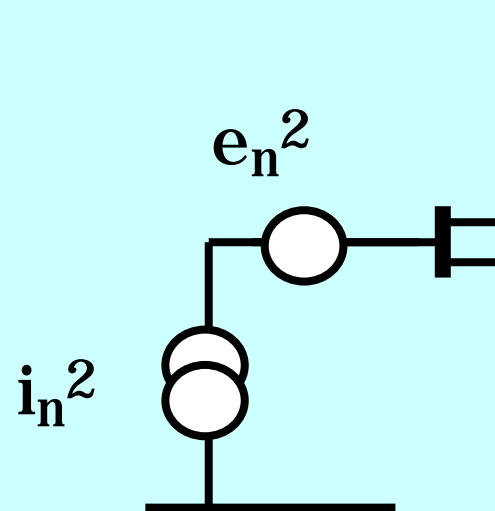
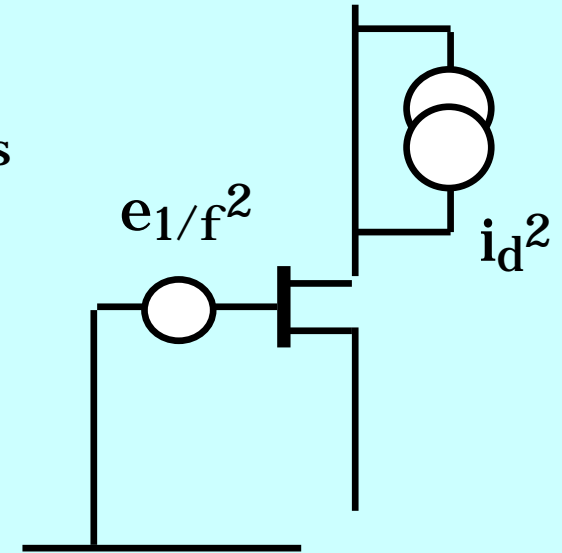
1/f noise e_n^2 A/f

- Transfer noise sources to input

$$i_d = g_m v_{gs} \Rightarrow e_n^2 = i_d^2 / g_m^2$$

$$e_n^2 = [4kT(2/3g_m) + A/f] f$$

$$i_n^2 = 0$$



MOSFET thermal noise

- Parameters are (almost) controlled by geometry and current alone

$$g_m = [2\mu C_{ox}(W/L)I_{DS}]^{1/2} \quad C_{ox} = \epsilon_{ox}/t_{ox}$$

$$e_n^2 = 4kT(2/3g_m) \quad f \sim 1/g_m$$

- How to get large g_m ?

Increase I_{DS} - but $e_n \sim I^{-1/4}$ power is a concern

Increase C_{ox} - it scales with technology feature size so modern processes help

1980 $\sim 10\mu\text{m}$ 2000 $\sim 0.25\mu\text{m}$ for L_{\min} $0.25\mu\text{m}$ $t_{ox} \sim 5\text{nm}$

Make W/L large

W can be made very large, eg 2-3mm

L can be minimum feature size

Cooling - can gain small amount - but device heats

- Caveat carrier mobility μ - unfortunately not a constant

carriers typically approach saturation velocity at high electric fields

$1\text{V}/0.25\mu\text{m} = 4 \times 10^4 \text{ V/cm}$ so $\mu = v/E$ falls as transistors shrink

MOSFET 1/f noise

- $e_{1/f}^2 = A_f/f$

$$A_f = K_f/[WL(C_{ox})^2]$$

K_f is technology dependent $K_f \sim 10^{-30} - 10^{-32} \text{ C.cm}^{-2}$

PMOS transistors are significantly better than NMOS

- **Corner frequency**

f_{corner} where $e_{\text{thermal}} = e_f$ typically $\sim 10\text{-}1000\text{kHz}$

dependent on technology details, device dimensions

JFET Noise

- Almost identical to MOSFET

- - differences are

Negligible $1/f$ noise - channel is buried below surface

Small gate current - gate is p-n diode

both can be reduced by cooling

- JFET is interesting for high resolution spectroscopy

allows to employ long shaping time constants (low f)

because of the very low $1/f$ noise

- Noise sources referred to input

$$e_n^2 = 4kT(2/3g_m) f$$

$$i_n^2 = 2eI_g f$$

